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BESTAVALLE



U.S. **UTILITY** Patent Application

SCANNED SS

PATENT DATE

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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
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George Barclay Robert Heumann Edward Rutter Jung-Kuang Chen

High resolution photoresist compositions

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PTO-2040 12/99

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ISSUING CLASSIFICATION					
ORIGIN	AL	CROSS REFERENCE(S)			
CLASS	SUBCLASS -	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)		
INTERNATIONAL	L CLASSIFICATION				
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TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED		
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G	
☐ The term of this patent subsequent to (date)			<u> </u>	NOTICE OF ALI	LOWANCE MAILED	
has been disclaimed.	(Assistant Examiner) (Date)					
The term of this patent shall not extend beyond the expiration date						
of U.S Patent. No.				ISS	UE FEE	
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this patent have been disclaimed.	(Legal Instrume	nts Examiner)	(Date)			
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